AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A method ~~Method~~ for the production of an antifalsification identification element including ~~elements each comprised of~~ at least one layer reflecting electromagnetic waves, one spacer layer and one layer formed of metallic clusters, the method comprising:

applying a partial layer or an all-over layer which reflects electromagnetic waves onto a carrier substrate;

after said applying the layer which reflects electromagnetic waves, applying at least one partial polymeric layer and/or all-over polymeric layer of defined thickness onto the carrier substrate to form a spacer layer;

~~wherein onto a carrier substrate a partial or all-over layer reflecting electromagnetic waves and subsequently one or several partial and/or all-over polymeric layers of defined thickness are applied,~~

modifying the spacer layer by a process selected from a group consisting of a PVD process, a CVD process, and treatment with oxidizing fluids; and

applying a layer formed of metallic clusters onto the spacer layer, the layer formed of metallic clusters being produced by a method of vacuum technology or by solvent-based systems.

~~whereupon onto the spacer layer a layer formed of metallic clusters is applied, which is produced by means of a method of vacuum technology or out of solvent-based systems.~~

2. (Currently Amended) A method ~~Method~~ for the production of an antifalsification identification element including ~~elements each comprised of~~ at least one layer reflecting

electromagnetic waves, one spacer layer and one layer formed of metallic clusters, the method comprising:

applying a layer formed of metallic clusters onto a carrier substrate, the layer formed of metallic clusters being produced by a method of vacuum technology or by solvent-based systems;

~~wherein onto a carrier substrate a layer formed of metallic clusters is applied, which is produced by means of a method of vacuum technology or out of solvent-based systems, and~~

after said applying the layer formed of metallic clusters, applying at least one partial polymeric layer and/or all-over polymeric layer of defined thickness onto the carrier substrate to form a spacer layer;

~~subsequently one or several partial and/or all-over polymeric layers of defined thickness are applied,~~

modifying the spacer layer by a process selected from a group consisting of a PVD process, a CVD process, and treatment with oxidizing fluids; and

applying a partial layer or an all-over layer reflecting electromagnetic waves onto the spacer layer.

~~whereupon one partial or all-over layer reflecting electromagnetic waves is applied onto the spacer layer.~~

3. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein the layer reflecting electromagnetic waves and the polymeric layer are applied to the carrier substrate, the carrier substrate constituting a first carrier substrate,

wherein the layer formed of metallic clusters is applied to a second carrier substrate, and

wherein the first carrier substrate and the second carrier substrate are connected to form the antifalsification identification element after the layer formed of metallic clusters, the layer reflecting electromagnetic waves, and the polymeric layer have been applied to the respective carrier substrates.

~~a first carrier substrate a layer reflecting electromagnetic waves and subsequently a polymeric spacer layer is applied, and onto a second carrier substrate a cluster layer, wherein, first, by connecting the two carrier substrates thus coated, the antifalsification identification element is generated or can be detected.~~

4. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein ~~the cluster layer~~ a protective layer is ~~applied.~~ applied onto the layer formed of metallic clusters.

5. (Cancelled)

6. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein the ~~polymeric~~ spacer layer is structured through decrosslinking effects.

7. (Currently Amended) The method of ~~Method as claimed in~~ claim 6, characterized in that the decrosslinking structures of the ~~structured polymeric~~ spacer layer are converted into unique codes by means of fingerprint algorithms.

8. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein the ~~polymeric~~ spacer layer is modified by treatment with sodium hypochlorite. ~~hypochlorite, through a PVD or a CVD process.~~

9. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein the ~~polymeric~~ spacer layer comprises a chromophore.

10. (Currently Amended) The method of ~~Method as claimed in~~ claim 1, wherein the ~~metallic cluster layer~~ layer formed of metallic clusters is deposited by sputtering or vapor deposition.

11. (Currently Amended) The method of ~~Method as claimed in~~ claim 2, wherein the layer formed of metallic clusters is applied to the carrier substrate, the carrier substrate constituting a first carrier substrate,

wherein the layer reflecting electromagnetic waves and the polymeric layer are applied to a second carrier substrate, and

wherein the first carrier substrate and the second carrier substrate are connected to form the antifalsification identification element after the layer formed of metallic clusters, the layer reflecting electromagnetic waves, and the polymeric layer have been applied to the respective carrier substrates.

~~a first carrier substrate a layer reflecting electromagnetic waves and subsequently a polymeric spacer layer is applied, and onto a second carrier substrate a cluster layer, wherein, first, by connecting the two carrier substrates thus coated, the antifalsification identification element is generated or can be detected.~~

12. (New) The method of claim 1, wherein said modifying the spacer layer is performed by a PVD process.

13. (New) The method of claim 1, wherein said modifying the spacer layer is performed by a CVD process.

14. (New) The method of claim 1, wherein said modifying the spacer layer is performed by treatment with oxidizing fluids.

15. (New) The method of claim 1, wherein said carrier substrate constitutes a first carrier substrate,

wherein said applying the layer formed of metallic clusters includes applying the layer formed of metallic clusters onto a second carrier substrate, and

wherein the first carrier substrate and the second carrier substrate are connected so as to form the antifalsification identification element after said applying the layer which reflects electromagnetic waves and said applying polymeric layer, and after said applying the layer formed of metallic clusters.

16. (New) The method of claim 2, wherein said modifying the spacer layer is performed by a PVD process.

17. (New) The method of claim 2, wherein said modifying the spacer layer is performed by a

CVD process.

18. (New) The method of claim 2, wherein said modifying the spacer layer is performed by treatment with oxidizing fluids.

19. (New) The method of claim 2, wherein said carrier substrate constitutes a first carrier substrate,

wherein said applying the layer reflecting electromagnetic waves includes applying the layer reflecting electromagnetic waves onto a second carrier substrate and wherein said applying the polymeric layer includes applying the polymeric layer onto the second carrier substrate, and

wherein the first carrier substrate and the second carrier substrate are connected so as to form the antifalsification identification element after said applying the layer which reflects electromagnetic waves and said applying polymeric layer, and after said applying the layer formed of metallic clusters.